

FORM PTO-1449 (Modified)

Attorney Docket No.  
14089-002520Serial No.:  
08/761,336LIST OF PATENTS AND PUBLICATIONS FOR  
APPLICANT'S INFORMATION DISCLOSURE  
STATEMENT  
65723 U.S. PTO

(Use several sheets if necessary)



Applicant: VIJAYEN VEERASAMY et al.

Filing Date:  
December 10, 1996Group:  
4316 1112

Reference Designation 04/14/97

## U.S. PATENT DOCUMENTS

Examiner Initial	Document No.	Date	Name	Class	Sub-class	Filing Date (If Appropriate)
AA	4,226,666	10/07/80	Winters et al.	156	643	08/21/78
AB	4,822,466	04/18/89	Rabalais et al.	204	192.15	06/25/87
AC	5,156,703	10/20/92	Oechsner	156	643	11/20/89
AD	5,182,132	01/26/93	Murai et al.	427	577	12/03/90
AE	5,423,915	06/13/95	Murata et al.	118	723	09/28/93
AF	5,462,784	10/31/95	Grill et al.	428	65.5	11/02/94
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)						
AG	Boxman, R.L. et al. "Recent Progress in Filtered Vacuum Arc Deposition," Paper submitted, Int. Conf. Metallurgical Coatings and Thin Films, San Diego, April 1996.					
AH	Veerasamy, V.S. et al. "Electronic Density of States in Highly Tetrahedral Amorphous Carbon," <u>Solid-State Electronics</u> , Vol. 37, No. 2, pp. 319-326, 1994.					
AI	Weiler, M. et al. "Preparation and Properties of Highly Tetrahedral Hydrogenated Amorphous Carbon," <u>Physical Review B</u> , Vol. 53, No. 3, pp. 1594-1608, 1996.					
AJ	Weiler, M. et al. "Structure of Amorphous Hydrogenated Carbon: Experiment and Computer Simulation," <u>Diamond and Related Materials</u> , Vol. 3, pp. 245-253, 1994.					
AK	Chhowalla, M. et al. "Deposition of Smooth Tetrahedral Amorphous Carbon Thin Films Using a Cathodic Arc Without a Macroparticle Filter," <u>Appl. Phys. Lett.</u> , Vol. 67, No. 7, pp. 894-896, 1995.					
AL	Chhowalla, M. et al. "Stationary Carbon Cathodic Arc: Plasma and Film Characterization," <u>J. Appl. Phys.</u> , Vol. 79, No. 5, pp. 2237-2244, 1996.					
AM	Oechsner, H. "Electron Cyclotron Wave Resonances and Power Absorption Effects in Electrodeless Low Pressure H.F. Plasmas with a Superimposed Static Magnetic Field," <u>Plasma Physics</u> , Vol. 16, pp. 835-844, 1974.					
AN	Oechsner, H. et al. "An RF Plasma Beam Source for Thin Film and Surface Technology," <u>Proc. 1st Int. Conf. on Plasma Surface Engineering, Garmisch Partenkirchen</u> , 1988, Vol. II, DGM Informationen Gesellschaft, Obvuroel, pp. 1017-1024, 1989.					
AO	Pfeiffer, B. "Skin Effect in Anisotropic Plasmas and Resonance Excitation of Electron-Cyclotron Waves. I. Theory," <u>Journal of Applied Physics</u> , Vol. 37, No. 4, pp. 1624-1627, 1966.					
AP	Sager, O. "The Influence of Nonuniform Density Distribution and Electron Temperature on the Helicon-Resonances in Low Pressure Discharges," 1971.					
AQ	Szuszczewicz, Edward P., "Spatial Distributions of Plasma Density in a High-Frequency Discharge with a Superimposed Static Magnetic Field," <u>The Physics of Fluids</u> , Vol. 15, No. 12, pp. 2240-2246, 1972.					
AR	Weiler, M. et al. "Highly Tetrahedral, Diamond-like Amorphous Hydrogenated Carbon Prepared from a Plasma Beam Source," <u>Appl. Phys. Lett.</u> , Vol. 64, No. 23, pp. 2797-2799, 1994.					
AS	Thesis by Manfred Weiler, 1989.					
AT	Dissertation by Manfred Weiler, 1994.					

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		Filing Date: December 10, 1996		Group: 1316		
___ AU	Dissertation by Dieter Martin, 1995.					
___ AV	Thesis by Franz Schön, 1968.					
___ AW	Thesis by Armin Fuchs, 1987.					
___ AX	Dissertation by Vijayen S. Veerasamy, 1994.					
<b>FOREIGN PATENT DOCUMENTS</b>						
	Document No.	Date	Country	Class	Sub-class	Translation (yes/no)
___ AY	0 595 564 A2	05/04/94	Europe	G11B	5/72	N/A
___ AZ	EP 0 700 033 A2	03/06/96	Europe	G11B	5/31	N/A
___ BA	5-143971	06/11/93	Japan	G11B	5/72	No
___ BB	6-139560	05/20/94	Japan	G11B	5/72	No
EXAMINER		DATE CONSIDERED				

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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